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(71) Applicant: **FOCUS-EBEAM TECHNOLOGY**

(BEIJING) CO., LTD. [CN/CN]; Room 8101, No. 3 Building, Yongchang Industrial Park, No. 3, Yongchang North Road, BDA, Beijing 100176 (CN).

(72) Inventors: **LI, Shuai**; Room 8101, No. 3 Building, Yongchang Industrial Park, No. 3, Yongchang North Road, BDA, Beijing 100176 (CN). **HE, Wei**; Room 8101, No. 3 Building, Yongchang Industrial Park, No. 3, Yongchang North Road, BDA, Beijing 100176 (CN).

(74) Agent: **CHINA PAT INTELLECTUAL PROPERTY OFFICE**; 2nd Floor, Zhongguancun Intellectual Property Building, Block B, No.21 Haidian South Road Haidian District, Beijing 100080 (CN).

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(54) Title: LOW-ENERGY SCANNING ELECTRON MICROSCOPE SYSTEM, SCANNING ELECTRON MICROSCOPE SYSTEM, AND SPECIMEN DETECTION METHOD

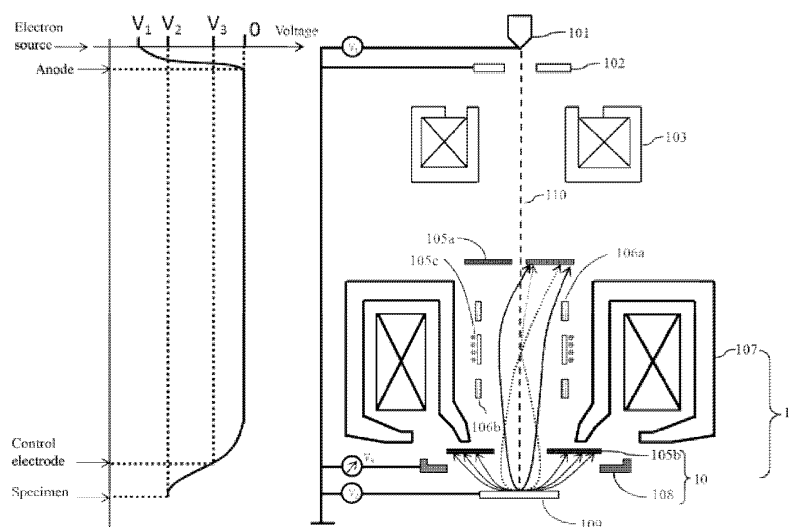


FIG. 1

(57) Abstract: A low-energy scanning electron microscope system includes an electron source, to generate an electron beam; an electron acceleration structure, to increase a motion velocity of the electron beam; a composite objective lens, to converge the electron beam accelerated by the electron acceleration structure; a deflection device, to change a motion direction of the electron beam; a detection device, to receive secondary electrons and back-scatter electrons generated when the electron beam acts on a specimen and to receive the back-scatter electrons, and a control device to change motion directions of the secondary electrons and the back-scatter electrons; and an electro lens, including the second sub-detection device, a specimen stage, and a control electrode, and to reduce the motion velocity of the electron beam and change the motion directions of the secondary electrons and the back-scatter electrons. A scanning electron microscope objective lens system and a specimen detection method is also provided.

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